

IFICDB (IFI Comprehensive Database)

Subject Coverage	<ul style="list-style-type: none"> • Chemistry • Engineering • Medicine • Nuclear Science • Technology
File Type	Bibliographic
Features	<p>Thesauri Controlled term (/CT) Thesaurus Fragment Code (/FG) Thesaurus Uniterm (/UN) Thesaurus International Patent Classification (/IPC) Thesaurus</p> <p>Alert (SDIs) Every update, weekly, or monthly (monthly is the default)</p> <p>CAS Registry Numbers® <input checked="" type="checkbox"/> Page Images <input type="checkbox"/> STN AnaVist <input type="checkbox"/></p> <p>Keep & Share <input checked="" type="checkbox"/> SLART <input checked="" type="checkbox"/> STN Easy <input checked="" type="checkbox"/></p> <p>Learning Database <input type="checkbox"/> Structures <input type="checkbox"/> STN Viewer <input type="checkbox"/></p>
Record Content	<ul style="list-style-type: none"> • Front page and bibliographic data, abstracts and claims from U.S. patents. • Standard bibliographic and patent data; USPTO Classifications (original and cross references), and issue dates. Front page patent abstracts, application data, priority data, and International Patent Classification (IPC) codes. • For records prior to January 25, 2011, CA references and CAS Registry Numbers are included for many of the chemical patents. Indexing by Uniterms is provided for chemical patents. Fragment codes, which allow for substructure searching of chemical substances, and Role indicators for chemical substances are also included.
File Size	More than 8.44 million records (11/11)
Coverage	Chemical and chemically related patents are covered from 1950 to the present. Mechanical and electrical patents from 1963 to the present. Design patents are covered from 1980 to the present. US applications published since March 15, 2001, are also included.
Updates	Twice a week.
Language	English
Database Producer	IFI CLAIMS® Patent Services, a division of Fairview Research LLC P.O. Box 1148, Madison, CT 06443 Phone: (203) 779-5301 Fax: (203) 583-4521 Email: info@ificlaims.com Copyright Holder

Sources United States patents issued by the U.S. Patent and Trademark Office since 1950 and announced in the U.S. Patent Office Official Gazette.

- User Aids**
- Online Helps (HELP DIRECTORY lists all help messages available)
 - STNGUIDE
 - Assignee List (available from the producer)
 - Compound Term List (available from the producer)
 - Fragment Terms List (available from the producer)
 - General Term List (available from the producer)
-

Clusters None

Pricing See the [STN Price List](#) or enter HELP COST at an arrow prompt (=>).

Search and Display Field Codes

Fields that allow left truncation are indicated with an asterisk (*).

Search Field Name	Search Code	Search Examples	Display Codes
Basic Index* (contains single words from the title (TI), abstract (AB), patent claims (ECLM, ACLM), government interest statement (GOVI), botanical information (BOTI), graphics information (GI), and note (NTE) fields, as well as CAS Registry Numbers (RN))	None (or /BI)	S ACETAL? S GOLF(A)CLUB AND DESIGN S SOFTWARE/BI S ELEVATION VIEW# S ROSA HYBRIDA S GRANT NUMBER S INDEXED FROM APPLICATION S 50-02-2 S ?POLAR?	AB, ACLM, BOTI, ECLM, GI, NTE, RN, TI
Abstract *	/AB	S MODEL?/AB S ?ACTION?/AB	AB
Accession Number (1)	/AN	S 2758301/AN	AN
Agent (Legal Representative)	/AG (or /LREP)	S SPENCER & FRANK/AG	AG
Application Country (2)	/AC	S US/AC AND 2000/AY S WO/AC	AI
Application Date (1,2)	/AD	S 19770603/AD S JUN 3 1997/AD	AI
Application Number (2,3)	/AP	S US199-609476/AP S 1996US-609476/AP S WO1991-AU272/AP	AI
Application Year (1,2)	/AY	S 1999/AY	AI
Art Unit (1)	/ARTU	S 123/ARTU	ARTU
Claims*	/CLM	S ?DRUGS?/CLM	ECLM, ACLM
Controlled Term (4)	/CT	S ACETIC ACID/CT	CT
Controlled Term, Business Methods	/CT.BM	S PACKAGE TRACKING/CT.BM	CT
Disclaimer Date (1)	/DCD	S DCD>=20020100	DCD
Document Type (code and text)	/DT (or /TC)	S REISSUE/DT S RR/DT S PATENT APPLICATION?/DT	DT
Entry Date (1)	/ED	S L1 AND ED>=20020700	ED
Examiner Name	/EXNAM	S ROBERTS?/EXNAM	EXNAM
Examiner's Field of Search	/EXF	S 430123000/EXF	EXF
Expiration Date (1)	/XPD	S L1 AND XPD>=19980100	XPD
Expiration Year (1)	/XPY	S L1 AND XPY>=1999	XPY
Family Member Country	/FC	S DE/FC	FI
Family Member Date (1)	/FD	S 20000104/FD	FI
Family Member Number (3)	/FN	S US30870/FN S US--30870/FN	FI
Family Member Year (1)	/FY	S FY>1998	FI
Field Availability	/FA	S L1 AND CLM/FA S AB/FA AND L7	Not displayed
File Segment (code and text)	/FS	S CHEMICAL/FS S C/FS S (C AND OS)/FS S L1 AND APPLICATION/FS S (CE AND GRANTED)/FS	FS
Fragment Code (4)	/FG	S 37730/FG (L) 30/RL	FG
International Patent Classification (IPC)(includes Main and Secondary IPCs)	/IC	S A24B/IC	IC, ICM, ICS
Inventor (includes location)	/IN (or /AU)	S FLINT?/IN S FLINT ALAN G/IN S (GREEN, A? (S) GB)/IN	IN

Search and Display Field Codes (cont'd)

Search Field Name	Search Code	Search Examples	Display Codes
Inventor in Nonstandard Format (includes location)	/INF	S CREETH/INF S (GLASSER (S) VA)/INF	INF
IPC Action Date (1)	/IPC.ACD	S 20061228/IPC.ACD	IPC, IPC.TAB
IPC Keyword	/IPC.KW	S ADVANCED/IPC.KW	IPC, IPC.TAB
IPC Old (IC, ICM, ICS)	/IPC.OLD	S A24B/IPC.OLD	IPC, IPC.TAB
IPC Version	/IPC.VER	S 20060101/IPC.VER	IPC, IPC.TAB
IPC, Initial	/IPCI	S A61K0009-14/IPCI	IPCI
IPC, Main	/ICM	S A01N001/ICM S A01N-001/02/ICM S 10-20/MGR (S) C07C/IC	IC, ICM
IPC, Main Group, Range- Searchable (1)	/MGR		IC, ICM, ICS
IPC, Reclassified	/IPCR	S A61K0009-14/IPCR	IPCR
IPC, Secondary	/ICS	S A01G027/ICS	IC, ICS
IPC, Subgroup, Range- Searchable (1)	/SGR	S SGR=>30000(S)C01B031/IC	IC, ICM, ICS
Issue National Patent Classification Code	/INCL	S 424093100/INCL	INCL
Issue Main National Patent Classification Code	/INCLM	S 424234100/INCLM	INCLM, INCL
Issue Secondary National Patent Classification Code	/INCLS	S 424200100/INCLS	INCLS, INCL
Language (code and text)	/LA	S EN/LA AND ABBOTT?/EXNAM	Not displayed
Main National Patent Classification Code	/NCLM	S 003001000/NCLM	NCL, NCLM
National Patent Classification Code (includes main and secondary NCLs)	/NCL	S 002002500/NCL	NCL, NCLM, NCLS
National Patent Classification, Range-Searchable (1)	/NCLR	S 2002000-20640000/NCLR	NCL, NCLM, NCLS
Note	/NTE	S APPLICATION/NTE	NTE
Number of Claims (1)	/CLMN	S 10-13/CLMN	CLMN
Number of Patents Citing This Patent	/PNC.G	S PNC.G>5	PI
Other Source	/OS	S CA/OS	OS
Patent Assignee (Probable)	/PPA	S ABBOTT/PPA	PPA
Patent Assignee (5) (includes patent assignee code)	/PA (or /CS)	S ABBOTT?/PA S MERRELL DOW/PA S 152/PA	PA
Patent Assignee in Nonstandard Format (includes location)	/PAF	S LEINER/PAF S NUTRITIONAL PRODUCTS/PAF S (HEWLETT-PACKARD(S)CA)/PAF	PAF
Patent Country (2)	/PC	S US/PC AND PY>1999 S WO/PC	PI
Patent Kind Code	/PK	S A1/PK	PI
Patent Number (2,3)	/PN	S US30843/PN S US--30843/PN S WO9200563/PN S US2002026659/PN	PI
Patent Number/Kind Code	/PNK	S US30843/PNK	PNK
Priority Country	/PRC	S DE/PRC	PRAI
Priority Date (1)	/PRD	S 19950109/PRD	PRAI
Priority Number (3,6) (includes provisionals)	/PRN	S DE1998-29801192/PRN S US2000-1429749/PRN	PRAI
Priority Year (1)	/PRY	S 1995-2000/PRY	PRAI
Publication Date (1)	/PD	S 20020702/PD	PI
Publication Year (1)	/PY	S 2001-2003/PY	PI
Reference Non-Patent Information	/REN	S XEROGRAPHY/REN	REN

Search and Display Field Codes (cont'd)

Search Field Name	Search Code	Search Examples	Display Codes
Reference Patent Classification	/RPCL	S D01101000/RPCL	REP
Reference Patent Country	/RPC	S AU/RPC	REP
Reference Patent Inventor	/RPIN	S PETROPOULOS?/RPIN	REP
Reference Patent Number (7)	/RPN	S AT24742/RPN	REP
Reference Patent Publication Date (1)	/RPD	S JUL 1990/RPD	REP
Reference Patent Publication Year (1)	/RPY	S 1995-1998/RPY	REP
Related Application Country	/RLC	S US/RLC	RLI
Related Application Date (1)	/RLD	S 19790407/RLD	RLI
Related Application Number (3)	/RLN	S US1956-626211/RNL S 1956US-0626211/RLN	RLI
Related Application Type (code and text)	/RLT	S CIP/RLT S CONTINUATION-IN-PART/RLT	RLI
Related Application Year (1)	/RLY	S 1988-1990/RLY	RLI
Related Patent Number (3)	/RLPN	S US3753535/RLPN	RLI
Related Publication Indicator (code and text)	/RLP	S ABD/RLP S ABANDONED/RLP	RLI
Role Indicator	/RL	S 20/RL S 50437/UN (S) 30/RL S 37730/FG (L) 30/RL S 021054000R/NCLS	CT, FG, UN
Secondary National Patent Classification Code	/NCLS		NCL, NCLS
Term of Patent (1)	/PTERM	S 13-15/PTERM	PTERM
Title*	/TI	S EPOXY TAPE/TI	TI
Uniterm (4)	/UN	S 00032/UN S 50437/UN (S) 30/RL	CT, UN
Uniterm Registry Number	/URN	S 50-00-0/URN	URN
Update Date (1)	/UP	S L1 AND UP>20020000	ED

- (1) Numeric search field that may be searched with numeric operators or ranges.
 (2) Data for PCT applications have been available in this field since late 1993; prior to 1993, PCT information is included in the abstracts.
 (3) Either STN format or Derwent format may be used.
 (4) There is a thesaurus-like feature available in this field. When you search a term in this field, the code and text are displayed automatically.
 (5) Search with implied (S) proximity is available in this field.
 (6) U.S. Provisional Priority Applications are searched only with the P appended.
 (7) Only non-US patent numbers are searchable in this field.

Super Search Fields

Enter a super search code to execute a search in one or more fields that may contain the desired information. Super search fields facilitate crossfile and multifile searching. EXPAND may not be used with super search fields. Use EXPAND with the individual field codes instead.

Search Field Name	Search Code	Fields Searched	Search Examples	Display Codes
Patent Application Group (1)	/APPS	/AP, /PRN, /RLN	S US56-626454/APPS S 56US-0626454/APPS	AI, PRAI, RLI
Patent Assignee Group	/PASS	/PA, /PAF, /PPA	S ABBOTT/PASS	PASS
Patent Countries	/PCS	/FC, /PC, /RPC	S DE/PCS	FI, PI, REP
Patent Numbers Group (1)	/PATS	/FN, /PN, /RPN	S US102601/PATS S US0102601/PATS	FI, PI, REP

- (1) Either STN format or Derwent format may be used.

IFICDB**Controlled Term (/CT) Thesaurus**

A thesaurus-like feature is available in the Controlled Term (/CT) field. When you search a term in this field, the code and the text are automatically displayed. To view the code and text, use the ALL Relationship Code in the EXPAND command.

Code	Content	Example
ALL	Code and Text (SELF, UN)	E ACID CATALYSTS+ALL/CT

Fragment Code (/FG) Thesaurus

A thesaurus-like feature is available in the Fragment Code (/FG) field. When you search a term in this field, the code and the text are automatically displayed. To view the code and text, use the ALL Relationship Code in the EXPAND command.

Code	Content	Example
ALL	Code and Text (SELF, CT)	S 30028+ALL/FG

Uniterm (/UN) Thesaurus

A thesaurus-like feature is available in the Uniterm (/UN) field. When you search a term in this field, the code and the text are automatically displayed. To view the code and text, use the ALL Relationship Code in the EXPAND command.

Code	Content	Example
ALL	Code and Text (SELF, CT)	E 00032+ALL/UN

International Patent Classification (/IPC) Thesaurus

IPC Thesaurus: The classifications and catchwords for the main headings and subheadings from the current (8th) edition of the WIPO International Patent Classification (IPC) manual are available. The classifications from the previous editions (1-7) are also available as separate thesauri. To EXPAND and SEARCH in the thesauri for editions 1-7, use the field code followed by the edition number, e.g., /IPC2, for the 2nd edition. Catchwords are included only in the thesauri for the 8th, 7th, 6th, and 5th editions.

All relationship codes can be used with both the SEARCH and EXPAND commands.

Relationship Code	Content	Example
ADVANCED (ADV)	Advanced Codes for the Core Level IPC code	E A61K0006-02+ADV/IPC
ALL	All Associated Terms (BT, SELF, NT, RT)	E H01B0001-06+ALL/IPC
BRO (MAN)	Complete Class	E H01B0017-54+BRO/IPC
BT	Broader Terms (SELF, BT)	E C01F0001-00+BT/IPC
CORE (COR)	Core Codes for the Advanced Level IPC code	E C03B0001-00+CORE/IPC
ED	Complete title of the SELF term and IPC manual edition	E C01F0001-00+ED/IPC
HIE	Hierarchy Terms (Broader and Narrower Terms) (BT, SELF, NT)	E C01C0003-00+HIE/IPC
INDEX	Complete title of the SELF term	E C01F0001-00+INDEX/IPC
KT	Keyword Terms (catchwords) (SELF, KT)	E INJECTION+KT/IPC
NEXT	Next Classification	E C01C0001-00+NEXT5/IPC
NT	Narrower Terms (SELF, NT)	E C01C+NT/IPC
PREV	Previous Classification	E C01C0001-12+PREV10/IPC
RT (SIB)	Related Terms (SELF, RT)	E C01C0003-20+RT/IPC
TI	Complete Title of the SELF Term and Broader Terms (BT, SELF)	E C01F0001-00+TI/IPC

DISPLAY and PRINT Formats

Any combination of display formats may be used to display or print answers. Multiple codes must be separated by spaces or commas, e.g., D L3 1-10 TI,AB or D L3 1-10 TI AB. The fields are displayed in the order requested.

Hit-term highlighting is available in all fields except AI, CDAT, FI, PI, PRAI, REP, RLI, UN, and XPD. Highlighting is set ON by default and must be ON when SEARCH is performed in order to use the HIT, KWIC, and OCC formats.

Format	Content	Examples
AB	Abstract	D 1-3 AB
AG, (LREP)	Agent (Legal Representative)	D 4 9 AG
AI (AP) (1)	Application Information	D L3 5-7 AI
AN (2)	Accession Number	D L3 AN 1-5
ARTU (2)	Art Unit	D ARTU L8
BOTI	Botanical Information	D BOTI
CDAT	Correction Date	D CDAT
CLMI (2)	Independent Claim Numbers	D 6 CLMI
CLMN (2)	Number of Claims	D 4 CLMN EXF
CT (2)	Controlled Term	D 1-3 CT L4
DCD	Disclaimer Date	D L3 6,8 DCD
DT (TC)	Document Type	D 1-4 DT
ECLM	Exemplary Claim	D L9 ECLM 3-6
ED (UP)	Entry Date (includes Update date)	D ED
EXF (2)	Examiner's Field of Search	D EXF 2,6-10
EXNAM	Examiner Name	D 7 L3 EXNAM
FG (2)	Fragment Code	D 3-10 FG
FI (FN) (1)	Family Information	D 1-5, 10 FI
FS	File Segment	D 1,5,8 FS
GI	Graphics Information	D GI 4-8,11
GOVI	Government Interest	D L14 GOVI
ICM (2)	IPC, Main	D 1-4 L2 ICM
ICS (2)	IPC, Secondary	D 5-6 L1 ICS
IN (AU)	Inventor (INF, IN)	D L4 1-6 IN
INCLM (2)	Issue Main National Patent Classification Code	D INCLM
INCLS (2)	Issue Secondary National Patent Classification Code	D INCLS
IPC.HIT (2)	HIT IPC codes	D IPC.HIT
IPC.UNIQ (2)	Unique IPC codes in record	D IPC.UNIQ
IPCI	IPC Initial	D IPCI
IPCR	IPC Reclassified	D IPCR
MFN (3)	Microfilm Frame Number (includes MRN)	D MFN
MRN (3)	Microfilm Reel Number (includes MFN)	D MRN
NCLM (2)	Main National Patent Classification Code	D L5 1-4 NCLM
NCLS (2)	Secondary National Patent Classification Code	D 1,5 L4 NCLS
NTE	Note	D NTE
OS	Other Source	D 2,5 OS
PA (CS)	Patent Assignee (PAF, PA)	D L2 1-3 PA
PARN	Parent Case Data	D 1-3 PARN
PI (PN) (1)	Patent Information	D 1,5,10 PI
PNK	Patent Number/Kind Code	D PNK
PPA	Patent Assignee (Probable)	D PPA
PRAI (PRN) (1)	Priority Information	D PRAI
PTERM	Term of Patent	D PTERM 5
REN	Reference Non-Patent Information	D 2 7 REN
REP (RPN) (1)	Reference Patent Information	D 6,12 L1 REP
RLI (RLN) (1)	Related Application Information	D 1-2 RLI
RN (2)	CAS Registry Number	D 1-5 RN
TI (2)	Title	D TI
UN (2)	Uniterm	D UN
URN (2)	Uniterm CAS Registry Number	D 1-4 URN
XPD	Expiration Date	D XPD
ABS	AB, NTE, CLMN	D ABS

DISPLAY and PRINT Formats (cont'd)

Format	Content	Examples
ALL (1,3)	AN, TI, INF, IN, PAF, PA, PPA, EXNAM, AG, PI, AI, PTERM, DCD, XPD, RLI, PRAI, FI, DT, CDAT, FS, OS, ED, GOVI, MRN, MFN, AB, NTE, BOTI, CLMN, GI, ECLM, ACLM, REP, REN, NCL (NCLM, NCLS), IPC, EXF, ARTU, RN	D 3 ALL
ALLTX (1,3)	ALL, including text for UN and FG	D ALLTX 3-5
APPS (1)	AI, RLI, PRAI	D APPS
BIB (1,3)	AN, TI, INF, IN, PAF, PA, PPA, EXNAM, AG, PI, AI, PTERM, DCD, XPD, RLI, PRAI, FI, DT, CDAT, FS, OS, ED, GOVI, MRN, MFN, NTE, BOTI, CLMN	D 1,4-6 BIB
CBIB (1,3)	AN, Compressed Bibliographic Data	D CBIB
CLM	Claims (ECLM, ACLM)	D CLM
DALL (1,3)	ALL, delimited for post processing	D DALL
IABS (1,3)	AB with a text label and CLMN indented with text labels	D 5 IABS
IALL (1,3)	ALL, indented with text labels	D IALL 5
IBIB (1,3)	BIB, indented with text labels	D CLM IBIB
IC (2)	International Patent Classification (ICM, ICS)	D 3,5,7 IC
ICLM	CLM with text labels	D ICLM TI 4
IIND (2)	IND, indented with text labels	D 1,6 IIND IRE
INCL	Issue National Patent Classification Code (INCLM, INCLS)	D INCL
IND (2)	NCL (NCLM, NCLS), IC (ICM, ICS), EXF, ARTU, RN, UN, URN, FG	D L2 1-20 IND
INDTX (2)	IND, including text for UN and FG	D L3 4 INDTX
IPC (2)	International Patent Classification (ICM, ICS, IPCI, IPCR)	D3,5,7 IPC
IPC.TAB (2)	IPC in Tabular Format	D IPC.TAB
IRE (1)	RE, indented with text labels	D 2-5 IRE
ISBIB (1,3)	SBIB, indented with text labels	D L3 ISBIB
ISTD (1,3)	STD, indented with text labels	D ISTD
ISTDN (1,3)	STDN, indented with text labels	D ISTDN
ITRIAL (2)	TRIAL, indented with text labels	D TRIAL
NCL (2)	National Patent Classification Code (NCLM, NCLS)	D NCL
PASS	PA, PAF, PPA	D PASS
PATS (1)	PI, RLI, FI, REP	D PATS
RE (1)	REP, REN	D RE 8,11
SBIB (1,3)	AN, TI, IN, PA, PPA, PI, AI, RLI, PRAI, FI, DT, CDAT, FS, OS, BOTI, MRN, MFN, CLMN (SBIB is the default)	D SBIB 3 L2
SCAN (2)	AN, TI, CLMN, INCL, INCLS, NCL, NCLM, NCLS, IPC, ICM, ICS, RN, UN, URN, FG (random display without answer number)	D SCAN
STD (1,3)	AN, TI, IN, PA, PPA, PI, AI, RLI, PRAI, FI, DT, CDAT, FS, OS, MRN, MFN, NCL (NCLM, NCLS), IPC (ICM, ICS, IPCI, IPCR)	D STD
STDN (1,3)	AN, TI, IN, PA, PPA, PI, AI, RLI, PRAI, FI, DT, FS, CDAT, OS, MRN, MFN, AB, NTE, BOTI, CLMN, ECLM, NCL (NCLM, NCLS), IPC (ICM, ICS, IPCI, IPCR)	D L2 STDN 1-4
TRIAL (2) (TRI, SAM, FREE)	AN, TI, CLMN, NCL (NCLM, NCLS), IPC (ICM, ICS, IPCI, IPCR), RN, UN, URN	D TRIAL TOTAL
FP (1)	Front page format for PI, TI, INF, PAF, AI, PTERM, DCD, RLI, PRAI, REP, REN, EXNAM, AG, GOVI, AB, CLMN, GI	D L3 FP 12
FPALL (1)	Front page format for PI, TI, INF, PAF, AI, PTERM, DCD, RLI, PRAI, IPC (ICM, ICS, IPCI, IPCR), NCL (NCLM, NCLS), EXF, REP, REN, EXNAM, AG, GOVI, AB, CLMN, GI, ECLM, ACLM	D 1 4 FPALL
FPBIB (1)	Front page format for PI, TI, INF, PAF, AI, PTERM, DCD, RLI, PRAI, EXNAM, AG, GOVI, CLMN	D FPBIB 6
FPSTDN (1)	Front page format for PI, TI, INF, PAF, AI, PTERM, DCD, RLI, PRAI, REP, REN, EXNAM, AG, GOVI, AB, CLMN, ECLM, NCL (NCLM, NCLS), IPC (ICM, ICS, IPCI, IPCR)	D FPSTDN L8
HIT	Fields containing hit terms	D HIT
KWIC	Hit terms with 20 words on either side (KeyWord-In-Context)	D KWIC NOH
OCC (2)	Number of occurrences of hit terms and fields in which they occur	D OCC

DISPLAY and PRINT Formats (cont'd)

- (1) By default, patent, application, and priority numbers are displayed in STN format. To display them in Derwent format, enter SET PATENT DERWENT at an arrow prompt. To reset display to STN format, enter SET PATENT STN.
 (2) No online display fee for this format. (3) MRN and MFN data available from 1979 to the present.

SELECT, ANALYZE, and SORT Fields

The SELECT command is used to create E-numbers containing terms taken from the specified field in an answer set.

The ANALYZE command is used to create an L-number containing terms taken from the specified field in an answer set.

The SORT command is used to rearrange the search results in either alphabetic or numeric order of the specified field(s).

Field Name	Field Code	ANALYZE/ SELECT(1)	SORT
Abstract	AB	Y	N
Accession Number	AN	Y	N
Agent (Legal Representative)	AG	Y (3)	Y
Application Country	AC	Y (4)	Y
Application Date	AD	Y (4)	Y
Application Information	AI	Y (4,5,6)	Y
Application Number	AP	Y (4,6)	Y
Application Number Group	APPS	Y (4,6,7)	N
Application Year	AY	Y (4)	N
Art Unit	ARTU	N	Y
Author (Inventor)	AU	Y	Y
Botanical Information	BOTI	Y (2)	N
CAS Registry Number	RN	Y	N
Controlled Term	CT	Y	N
Corporate Source (Patent Assignee)	CS	Y	Y
Disclaimer Date	DCD	Y	Y
Document Type	DT	Y	Y
Examiner Name	EXNAM	Y	N
Examiner's Field of Search	EXF	Y	Y
Expiration Date	XPD	Y (4)	Y
Expiration Year	XPY	Y (4)	Y
Family Member Country	FC	Y (4)	N
Family Member Date	FD	Y (4)	N
Family Member Information	FI	Y (4,6,8)	N
Family Member Number	FN	Y (4,6)	N
Family Member Year	FY	Y (4)	N
File Segment	FS	Y	Y
Fragment Code	FG	Y	N
Inventor	IN	Y	Y
Inventor in Nonstandard Format	INF	Y	N
IPC	IPC	Y (9)	Y
	IC	Y (10)	Y
IPC Hit IPC codes	IPC.HIT	Y	Y
IPC Unique IPC codes in record	IPC.UNIQ	Y	Y
IPC, Initial	IPC.I	Y	N
IPC, Main	ICM	Y	Y
IPC, Reclassified	IPCR	Y	N
IPC, Secondary	ICS	Y	Y
Issue National Patent Classification Code	INCL	Y	Y
Issue Main National Patent Classification Code	INCLM	Y	Y
Issue Secondary National Patent Classification Code	INCS	Y	N
Legal Representative (Agent)	LREP	Y	Y
Main National Patent Classification Code	NCLM	Y	Y
Microfilm Frame Number	MFN	N	Y

SELECT, ANALYZE, and SORT Fields (cont'd)

Field Name	Field Code	ANALYZE/ SELECT(1)	SORT
Microfilm Reel Number	MRN	N	Y
National Patent Classification Code	NCL	Y (11)	Y
Note	NTE	Y (2)	N
Number of Claims	CLMN	N	Y
Occurrence of Hit Terms	OCC	N	Y
Other Source	OS	Y	Y
Patent Assignee (Probable)	PPA	Y	Y
Patent Countries Group	PCS	Y (4,13)	N
Patent Country	PC	Y (4)	Y
Patent Information	PI	Y (4,6,12)	Y
Patent Number	PN	Y (4,6)	Y
Patent Number Group	PATS	Y (4,6,14)	N
Patent Number/Kind Code	PNK	Y	N
Priority Country	PRC	Y (4)	Y
Priority Date	PRD	Y (4)	Y
Priority Information	PRAI	Y (4,6,15)	Y
Priority Number	PRN	Y (4,6)	Y
Priority Year	PRY	Y (4)	N
Publication Date	PD	Y (4)	Y
Publication Year	PY	Y (4)	Y
Reference Patent Classification	RPCL	Y (4)	N
Reference Patent Country	RPC	Y (4)	N
Reference Patent Information	REP	Y (4,6,16)	N
Reference Patent Inventor	RPIN	Y (4)	N
Reference Patent Number	RPN	Y (4,6)	N
Reference Patent Publication Date	RPD	Y (4)	N
Related Application Country	RLC	Y (4)	N
Related Application Date	RLD	Y (4)	N
Related Application Information	RLI	Y (4,6,17)	N
Related Application Number	RLN	Y (4,6)	N
Related Application Type	RLT	Y (4)	N
Related Application Year	RLY	Y (4)	N
Related Patent Number	RLPN	Y (4)	N
Secondary National Patent Classification Code	NCLS	Y	N
Term of Patent	PTERM	N	Y
Title	TI	Y (default)	Y
Treatment Code	TC	Y (18)	Y
Uniterm	UN	Y (4)	N
Uniterm Registry Number	URN	Y	N

- (1) HIT may be used to restrict terms extracted to terms that match the search expression used to create the answer set, e.g., SEL HIT RN.
- (2) Appends /BI to the terms created by SELECT.
- (3) Appends /LREP to the terms created by SELECT.
- (4) SELECT HIT and ANALYZE HIT are not valid with this field.
- (5) Selects or analyzes the application number with /AP appended to the terms created by SELECT.
- (6) Enter SET PATENT DERWENT at an arrow prompt (=>) to extract patent, application, priority, family, reference patent, and related application numbers in Derwent format.
- (7) Selects or analyzes application, priority, and related application numbers with /APPS appended to the terms created by SELECT.
- (8) Selects or analyzes family numbers with /FN appended to the terms created by SELECT.
- (9) Selects or analyzes all IPC codes with /IPC appended to the terms created by SELECT.
- (10) Selects or analyzes ICM and ICS with /IC appended to the terms created by SELECT.
- (11) Selects or analyzes NCLM and NCLS with /NCL appended to the terms created by SELECT.
- (12) Selects or analyzes the patent numbers with /PN appended to the terms created by SELECT.
- (13) Selects or analyzes the patent countries from PI, FI, and REP fields with /PCS appended to the terms created by SELECT.
- (14) Selects or analyzes the patent numbers from PI, FI, and REP fields with /PATS appended to the terms created by SELECT.
- (15) Selects or analyzes the priority numbers with /PRN appended to the terms created by SELECT.
- (16) Selects or analyzes the reference patent numbers with /RPN appended to the terms created by SELECT.
- (17) Selects or analyzes the related application numbers with /RLN appended to the terms created by SELECT.
- (18) Appends /DT to the terms created by SELECT.

Full-Text Browsing

User Request	Example	System Response
DISPLAY BROWSE	=> DISPLAY BROWSE ENTER (L1) OR L#:. ENTER (DIS), ANSWER NUMBERS, OR END:	NOVICE version
D BRO Answer number(s) Answer number(s) and format Format only *Format Forward n fields Backward n fields Search forward for a character string Search backward for a character string End DISPLAY BROWSE	=> D BRO L1 :1-3 :. :4 HIT :TI TX :*KWIC :F3 :B1 :S GROWTH REGUL :S :S- ALKANOIC ACID :S- :END =>	EXPERT version display answers 1, 2, and 3 in default format display next answer in default format display answer 4 in HIT format display title and text of last answer displayed change default to KWIC; no answer displayed move forward 3 fields move backward 1 field search forward within record for 'growth regul' repeat search forward for the current string search backward within record for 'alkanoic acid.' repeat search backward for the current string exit DISPLAY BROWSE and return to => prompt

12

IFICDB

Sample Records

EXPAND in /CT Thesaurus

```
=> E POLYISOBUTYLENE+ALL/CT
E1      6140  -->  POLYISOBUTYLENE/CT
                UN   04220
*****  END  *****
```

EXPAND in /UN Thesaurus

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=> E 04220+ALL/UN
E1      6140  -->  04220/UN
                CT   POLYISOBUTYLENE
*****  END  *****
```

EXPAND in /FG Thesaurus

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=> E 30038+ALL/FG
E1      10373 -->  30038/FG
                CT   CARBON, 1-8 (M) (STO)
*****  END  *****
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DISPLAY SBIB

```
AN      10139865  IFIPAT;IFIUDB;IFICDB
TI      Basidiomycete peroxidase gene-transferred plant and a method for
        decomposing and removing hazardous chemicals using the same; Transgenic
        plants for use in removing hazardous chemicals from the environment
IN      Iimura Yosuke; Katayama Yoshihiro
PA      Agency of Industrial Science & Technology JP (1064)
        Unassigned Or Assigned To Individual (68000)
        Record Has Multiple Assignees (92222)
PI      US-20020083492  A1  20020627
AI      2000US-000748264  20001227  (9)
PRAI    2000JP-000223653  20000726
FI      US-20020083492  20020627
        US-----6642439
DT      Utility; Patent Application - First Publication
FS      CHEMICAL
        APPLICATION
ED      Entered STN: 28 Jun 2002
        Last Updated on STN: 23 Mar 2003
CLMN    5
```

DISPLAY FPALL

United States Patent

Patent Number: 6413640
Kind Code: B1
Date of Patent: 20020702-----
CARBON FIBER COMPOSITE MATERIALS; FIBERS IN A SILICON/SILICON CARBIDE MATRIX:
FOR USE AS AEROSPACE MATERIALS WITH LOW OXYGEN-INDUCED MASS LOSS AND HIGH
DURABILITYInventor(s): Hanzawa; Shigeru, Kagamigahara, JP
Nakano; Kenji, Tokai, JP
Assignee: NGK Insulators, Ltd., Nagoya, JP
Appl. No.: US 2000-499004
Filed: 20000204

Priority Data

JP 1999-31979 19990209
JP 1999-313788 19991104
JP 2000-20003499 20000112Int. Cl. B32B009-00
U.S. Cl. 428408000; 428293100; 428293400; 428409000; 428688000;
428689000
Field of Search ... 428293100; 428293400; 428293700; 428408000; 428409000;
428688000; 428689000; 428898000

FOREIGN PATENT DOCUMENTS

Patent Number	Date	Class
EP 1028099	Aug 2000	
GB 1457757	Dec 1976	
WO 9919273	Apr 1999	

Primary Examiner - Jones, Deborah
Assistant Examiner - Bahta, Abraham
Attorney, Agent or Firm - Burr & Brown-----
ABSTRACT

Provided are carbon fiber composite materials which have a structure including a skeletal part and a matrix formed integrally around the skeletal part. The skeletal part is mainly composed of carbon fiber bundles and silicon carbide and metallic silicon formed in the carbon fiber bundles and/or on the outer surface of the carbon fiber bundles. The matrix is mainly composed of silicon carbide and metallic silicon. Alternatively, the carbon fiber composite materials have a structure including a skeletal part and a matrix formed integrally around the skeletal part and have a porosity of 0.5-5% and a two-peak type distribution of average pore diameter. The skeletal part is formed of carbon fibers and a carbon component other than the carbon fibers and/or silicon carbide, and the matrix being formed of silicon carbide at least 50% of which is of beta type. These carbon fiber composite materials are suitable for the uses as aerospace materials.

DISPLAY FPALL (cont'd)

8 Claim(s), 5 Drawing Sheet(s), 7 Figure(s).

EXEMPLARY CLAIM

D R A W I N G

1. A carbon fiber composite material which has a structure comprising a skeletal part and a matrix formed integrally around the skeletal part, said skeletal part being mainly composed of carbon fiber bundles and silicon carbide and metallic silicon formed in the carbon fiber bundles and/or on the outer surface of the carbon fiber bundles and said matrix being mainly composed of silicon carbide and metallic silicon, wherein the content of metallic silicon increases in an inclined manner from inside of the skeletal part toward the outer surface of the skeletal part, and/or from the outer surface of the skeletal part toward the outer surface of the matrix, and/or from the outer surface of the matrix toward the inside of the matrix.

NON-EXEMPLARY CLAIMS

2. A carbon fiber composite material which has a structure comprising a skeletal part and a matrix formed integrally around the skeletal part, said skeletal part being mainly composed of carbon fiber bundles and silicon carbide and metallic silicon formed in the carbon fiber bundles and/or on the outer surface of the carbon fiber bundles and said matrix being mainly composed of silicon carbide and metallic silicon, said material being formed by laminating a plurality of sheets each of which comprises a plurality of preformed yarns arranged in nearly parallel with one another, said preformed yarns comprising bundles mainly composed of carbon fibers and a resin covering the outer surface of the bundles, heat-treating the laminate in a non-oxidizing atmosphere, and impregnating the laminate with metallic silicon to form integrally the skeletal part and the matrix.

3. A carbon fiber composite material which has a structure comprising a skeletal part and a matrix formed integrally around the skeletal part and has a porosity of 0.5-5% and a two-peak type distribution of average pore diameter, said skeletal part being formed of carbon fibers and a carbon component other than the carbon fibers and/or silicon carbide, and said matrix being formed of silicon carbide at least 50% of which is of beta type.

4. A carbon fiber composite material according to claim 3, wherein the matrix is formed along the surface of the skeletal part.

5. A carbon fiber composite material according to claim 3, wherein the matrix has such an inclined composition as the silicon content increasing in proportion to the distance from the surface of the skeletal part.

6. A carbon fiber composite material according to claim 3, wherein the matrix has a continuous three-dimensional network structure.

7. A carbon fiber composite material according to claim 3, wherein the skeletal part comprises a laminate formed by laminating sheets each of which comprises a plurality of preformed yarns arranged in nearly parallel with each other and comprising carbon fibers and a carbon component other than carbon fibers in such a manner that the longer directions of the preformed yarns alternately cross at right angles.

8. A carbon fiber composite material according to claim 3, which is an aerospace material.

DISPLAY IALL

AN 3443624 IFIPAT;IFIUDB;IFICDB
TITLE: USE OF CARBON DIOXIDE AND CARBONIC ACID TO CLEAN
CONTACT LENSES; DISINFECTING HYDROGEN PEROXIDE IN
EFFERVESCENT TABLETS FOR CONTACT LENSES
INVENTOR(S): Ali; Yusuf, Hudson, OH
Bhatia; Rajkumar, Arlington, TX
Kulshreshtha; Alok K., Arlington, TX
Owen; Geoffrey R., Southlake, TX
PATENT ASSIGNEE(S): Alcon Laboratories, Inc., Fort Worth, TX
PRIMARY EXAMINER: Gulakowski, Randy
ASSISTANT EXAMINER: Chaudhry, Saeed
AGENT: Ryan, Patrick M.

	NUMBER	PK	DATE
PATENT INFORMATION:	US 6171404	B1	20010109
APPLICATION INFORMATION:	US 1999-296893		19990422
EXPIRATION DATE:	25 Feb 2017		

	APPLN. NUMBER	DATE	GRANTED PATENT NO. OR STATUS
CONTINUATION-IN-PART OF:	US 1997-806571	19970225	ABANDONED
CONTINUATION-IN-PART OF:	US 1998-99669	19980618	5909745

	NUMBER	DATE
PRIORITY APPLN. INFO.:	US 1996-12274P	19960226 (Provisional)
FAMILY INFORMATION:	US 6171404	20010109
	US 5909745	
DOCUMENT TYPE:	UTILITY	
	REASSIGNED	
FILE SEGMENT:	CHEMICAL	
	GRANTED	
OTHER SOURCE:	CA 134:79767	
ENTRY DATE:	Entered STN: 11 Jan 2001	
	Last Updated on STN: 8 Jul 2002	
MICROFILM REEL NO:	009984	FRAME NO: 0971

ABSTRACT:

Simple, efficacious, easily manufacturable, convenient to use and cost-effective contact lens care cleaning compositions comprising carbon dioxide and carbonic acid as cleansing agents are disclosed. The compositions do not require abrasive agents such as polymeric beads, nor ocularly irritating agents such as enzymes or surfactants in order to effectively clean proteinaceous and nonproteinaceous deposits from the surface of contact lenses. Also disclosed is a one-step cleaning and disinfecting regimen, whereby an effervescent tablet composition capable of generating carbon dioxide and carbonic acid is dissolved in a disinfecting solution or rinsing/disinfecting/storage solution.

NUMBER OF CLAIMS: 6
GRAPHICS INFORMATION: 1 Drawing Sheet(s), 1 Figure(s).
INDEPENDENT CLAIMS: 5,6

EXEMPLARY CLAIM(S):

D R A W I N G

DISPLAY IALL (cont'd)

1. A method of cleaning a soiled contact lens comprising the steps of dissolving an effervescent tablet composition capable of generating a cleansing amount of carbon dioxide and carbonic acid in an aqueous composition having a pH of less than about 7.5 to form a cleaning solution, and contacting the soiled lens with the cleaning solution for a time sufficient to clean the soiled lens, wherein the effervescent tablet composition excludes polymeric beads, an enzyme, a cleansing amount of a surfactant, and a disinfecting amount of hydrogen peroxide, and further provided that the effervescent tablet is a layered tablet comprising a first layer containing a compound selected from the group consisting of alkali carbonate compounds but lacking an acidic compound and a second layer containing a compound selected from the group consisting of organic and inorganic acidic compounds but lacking an alkali carbonate compound.

NON-EXEMPLARY CLAIM(S) :

2. The method of claim 1 wherein the first layer comprises an alkali carbonate compound selected from the group consisting of sodium carbonate, sodium bicarbonate, glycine carbonate, potassium carbonate, potassium bicarbonate, potassium dihydrogencitrate, and calcium carbonate; and the second layer comprises a compound selected from the group consisting of citric acid, adipic acid, tartaric acid, maleic acid, boric acid, benzoic acid, hydroxybenzoic acid, methoxybenzoic acid, mandelic acid, malonic acid, lactic acid, pyruvic acid, glutaric acid, aspartic acid, hydrochloric acid, oxalic acid, salicylic acid, succinic acid, and acetic acid.

3. The method of claim 2 wherein the first layer comprises sodium bicarbonate and the second layer comprises an acidic compound selected from the group consisting of citric acid, adipic acid and combinations of citric and adipic acids.

4. The method of claim 1 wherein the aqueous composition is selected from the group consisting of purified water; saline solutions; disinfecting solutions; and rinsing/disinfecting/storage solutions; provided that the aqueous composition does not contain a disinfecting amount of hydrogen peroxide.

5. A method of cleaning a soiled contact lens comprising the steps of dissolving an effervescent tablet composition in an aqueous composition having a pH of less than about 7.5 to form a cleaning solution, and contacting the soiled lens with the cleaning solution for a time sufficient to clean the soiled lens, wherein the effervescent tablet composition excludes polymeric beads, an enzyme, a cleansing amount of a surfactant, and a disinfecting amount of hydrogen peroxide, and further provided that only one of the effervescent tablet and the aqueous composition contains an alkali carbonate compound but no acidic component, and the other of the effervescent table and the aqueous composition contains an acidic component but no alkali carbonate compound, such that when the effervescent tablet is dissolved in the aqueous composition a cleansing amount of carbon dioxide and carbonic acid is generated.

6. A method of cleaning a soiled contact lens comprising contacting the soiled lens with an aqueous composition having a pH of less than about 7.5 comprising a cleansing amount of carbon dioxide and carbonic acid for a time sufficient to clean the soiled lens, wherein the composition excludes polymeric beads, an enzyme, a cleansing amount of a surfactant, and a disinfecting amount of hydrogen peroxide, and wherein the composition is formed by combining separately packaged first and second aqueous compositions, where the first aqueous composition comprises an alkali carbonate compound but lacks an acidic component selected from the group consisting of inorganic and organic acids, and the second aqueous composition comprises an acidic component selected from the group consisting of inorganic and organic acids but lacks an alkali carbonate compound.

DISPLAY IALL (cont'd)

CITED US REFERENCES: US 3855914 Dec 1974 099275000 Nishino et al.
 US 4361536 Nov 1982 422033000 Leopardi
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 US 5954889 Sep 1999 134006000 Wertheimer

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 EP 257942 Mar 1988
 EP 93784 Apr 1982
 JP 01179123 Jul 1989
 JP 57048712 Mar 1982
 JP 63264518 Nov 1988
 WO 9419027 Sep 1994
 WO 9620736 Jul 1996

ISSUE U.S. PATENT CLASSIF.:

MAIN: 134003000
 SECONDARY: 134042000; 510112000; 510117000

CURRENT U.S. PATENT CLASSIF.:

MAIN: 134003000
 SECONDARY: 134042000; 510112000; 510117000

INT. PATENT CLASSIF.:

MAIN: B08B003-08
 SECONDARY: C11D003-10

FIELD OF SEARCH: 134003000; 134025400; 134028000; 134042000;
 510112000; 510117000; 510120000

ART UNIT: 176

CONTROLLED TERMS: General Uniterms:

ABRASIVES 00007; ACIDITY 00040; ALKALINITY 00160; ANTIDEPOSIT AGENTS 00300;
 ANTISEPTICS 00334; BEADS 00538; CLEANING 01101; CLEANING COMPOUNDS 01102;
 CONSTRUCTION 01260; CONTACT LENSES 01264; DISSOLVING 01743; EFFERVESCENCE
 01869; EYES/BIOLOGICAL/ 02095; GENERATION 02434; MULTILAYER 03504; ONE STEP
 03754; PEROXIDATION 03966; PH 03986; POLYMERS AND RESINS/UNDEFINED/ 04230-10;
 PROTEINS 04440-10 20; RINSING 04731; SENSITIVITY 04914; SOILS 05112; SOLUTIONS 05137;
 STORAGE 05316; SURFACTANTS/NOT SPECIFIC/ 05398; TABLETS 05450; TIMES 05610;
 PROCESS 06232; CARBOXYLIC ACIDS 07181-10; ENZYMES/NOT SPECIFIC/ 07386-10 20;
 ENZYMES/CT/ 10003; PEROXY COMPOUNDS - INORGANIC/CT/ 10015; STABILITY/CT/ 10019;
 PURIFICATION OR SEPARATION/CT/ 10020; METAL FRAGMENTS - ORGANIC/CT/ 10102;
 POLYMER DESCRIPTORS/CT/ 10204;

Compound Uniterms:

SUBSTANCE NAME	UNITERM CODE	CAS REGISTRY NUMBER
ADIPIC ACID	50028-10	124-04-9
BENZOIC ACID	50106-10	65-85-0
CARBON DIOXIDE, CO2	50201-10	124-38-9
HYDROCHLORIC ACID, HCL	50344-10	7647-01-0
HYDROGEN PEROXIDE, H2O2	50347-10 20	7722-84-1
POTASSIUM CARBONATE, K2CO3	50544-10	584-08-7
SODIUM BICARBONATE, NAHCO3	50590-10	144-55-8
ACETIC ACID	50762-10	64-19-7
CITRIC ACID	50763-10	25779-93-5
OXALIC ACID	50767-10	144-62-7
SALICYLIC ACID	50802-10	69-72-7
SODIUM CARBONATE, NA2CO3	51197-10	497-19-8
CALCIUM CARBONATE, CACO3	51252-10	471-34-1
LACTIC ACID	51494-10	50-21-5
MALEIC ACID	52274-10	110-16-7Q, 6915-18-0Q, 110-17-8Q

IFICDB**DISPLAY IALL (cont'd)**

TARTARIC ACID	53268-10	87-69-4
POTASSIUM BICARBONATE, KHCO ₃	54316-10	298-14-6
SUCCINIC ACID	54552-10	110-15-6
GLUTARIC ACID	54604-10	110-94-1
MANDELIC ACID	54735-10	90-64-2
CARBONIC ACID, H ₂ CO ₃	57304-10	463-79-6
DIPOTASSIUM CITRATE	58026-10	
ASPARTIC ACID	58860-10	
BENZOIC ACID, P-HYDROXY-	60104-10	99-96-7
MALONIC ACID	63295-10	141-82-2
PYRUVIC ACID	64307-10	127-17-3
ANISIC ACID/P-/	86971-10	100-09-4
BORIC ACID, H ₃ BO ₃	98066-10	10043-

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Germany
Phone: +49-7247-808-555
Fax: +49-7247-808-259
E-mail: helpdesk@fiz-karlsruhe.de
Internet: www.stn-international.com

In Japan

JAICI (Japan Association for
International Chemical Information)
STN Japan
Nakai Building
6-25-4 Honkomagome, Bunkyo-ku
Tokyo 113-0021, Japan
Phone: +81-3-5978-3601 (Technical Service)
+81-3-5978-3621 (Customer Service)
Fax: +81-3-5978-3600
E-mail: support@jaici.or.jp (Technical Service)
customer@jaici.or.jp (Customer Service)
Internet: www.jaici.or.jp